PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q85504

Heiji WATANABE, et al.

Application. No.: 10/519,084

Group Art Unit: 2822

Confirmation No.: 7332

Examiner: Tsz K. CHIU

Filed: December 23, 2004

For:

SEMICONDUCTOR DEVICE AND ITS MANUFACTURING METHOD

STATEMENT OF SUBSTANCE OF INTERVIEW

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Please review and enter the following remarks summarizing the interview conducted on April 8, 2008:

REMARKS

An Examiner's Interview Summary Record (PTO-413) was dated April 14, 2008.

During the interview, the following was discussed with Examiner Chiu, and Supervisory

Examiner Rose:

- 1. Brief description of exhibits or demonstration: Not addressed
- 2. <u>Identification of claims discussed</u>: All the claims under consideration were

discussed.

3. <u>Identification of art discussed</u>: Park et al. (U.S. Patent No. 7,157,359) was

discussed.

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4. <u>Identification of principal proposed amendments:</u> Previously, claims had been

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amended to recite a gate electrode stacked on top of a high dielectric constant layer.

5. Brief Identification of principal arguments: The invention as disclosed in the

present invention consists of a gate electrode in direct contact with a high dielectric constant

layer. In comparison, Park discloses a semiconductor device that includes a metal barrier layer

between the metal electrode and a high dielectric constant layer.

6. Indication of other pertinent matters discussed: Not addressed.

7. Results of Interview: Examiner Chiu indicated that the rejections based on Chiu

could be overcome if the present claims were amended to incorporate stacking of the gate

electrode in contact with the high dielectric constant layer.

It is respectfully submitted that the instant STATEMENT OF SUBSTANCE OF

INTERVIEW complies with the requirements of 37 C.F.R. §§1.2 and 1.133 and MPEP §713.04.

It is believed that no petition or fee is required. However, if the USPTO deems

otherwise, Applicant hereby petitions for any extension of time which may be required to

maintain the pendency of this case, and any required fee, except for the Issue Fee, for such

extension is to be charged to Deposit Account No. 19-4880.

Respectfully submitted,

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Date: May 29, 2008

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